2017.5.12 QE

NEMS ENGG5404
1. Explain "scaling law", and what one two most commonly used actualizan in the microscale and explain why.
2. Explain thermal evaponation and sputtering, the proximal cons, when will you chance thermal evaponation
and when will you choose sputtering?
3. Defene APCVD, PECVD and LPCVD, what over the prosonal cons.
4. What are posterie photoresist and negative photoresist? Winder what commistance will you choose PR and will you choose NP?
5. In order to enhance the uniformalisty of the film, what will you do to design a CVD chamber?
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Smoot materials MAEG5080 1500
Legrange, desirve the equation of motion of the system of a separate of the system of
F2(t) M2
Nononaterals MAEG5120
1. Explain the two-photon phenomenon with schematr diagram.
2. What is the advantages of Two-photon microscopy over confacel laser scanning microscopy. Fist two
3. Calculate is the throat force for an ephoric microrabolis to movertain it's speed.

香港中文大學學生會:范克廉複地庫